

Abstract of the Disclosure

An apparatus processing a substrate, comprising a plurality of lift pins causing the substrate to move up and down, a first lifting mechanism causing the 5 plurality of lift pins to move up and down, a heating plate performing a heating process onto the substrate, having a plurality of holes causing the plurality of lift pins to protrude and sink there-through to a surface facing the substrate, a lid having an inside 10 portion and a outside portion, being disposed above the heating plate so that the inside portion faces the heating plate, and capable of moving up and down, a second lifting mechanism causing the lid to move up and down, a first inert gas introducing mechanism 15 introducing a first inert gas to the inside portion of the lid and a second inert gas introducing mechanism introducing a second inert gas onto the surface of the heating plate through the plurality of holes. In such a structure, nitrogen can be introduced to both a surface 20 and a rear side of the substrate, and oxygen is prevented from being forced to come around to the surface of the substrate from the rear side thereof. As a result, oxidation of the substrate can be prevented.